

PATENT OF INVENTION

"MAGNETIC ETCHING PROCESS, ESPECIALLY FOR MAGNETIC OR
MAGNETOOPTIC RECORDING"

ABSTRACT

Process for writing on a material, in which said material is irradiated by means of a beam of light ions, such as for example He^+ ions, said beam of light ions having an energy of the order of or less than a hundred keV, wherein this material comprises a plurality of superposed thin-layers, at least one of said thin layers being magnetic and in that one or more regions having sizes of the order of 1 micrometer or less are irradiated, the irradiation dose being controlled so as to be a few 10^{16} ions/cm² or less, the irradiation modifying the composition of atomic planes in the material at one or more interfaces between two layers of the latter.